

SEP 26 2006

SHEET 1 OF 1

Form PTO 1449  
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10/580,833

## LIST OF REFERENCES CITED BY APPLICANT

APPLICANT

Kazuhito YASUDA, et al.

FILING DATE

May 26, 2006

GROUP

## U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						

## FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
					YES	NO
	AO					
	AP					
	AQ					
	AR					
	AS					

## OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

/MG/	AT	NAKANISHI, Yutaro et al., "Growth and Electronic Properties of Thick CdTe Layers Grown on GaAs by MOVPE", Technical Report of IEICE., Vol. 103, No. 50, pgs. 81-85, 2003.				
/MG/	AU	MASUDA, Yusuke et al., "Arsenic Doping In CdTe Layers Grown by Metalorganic Vapor Phase Epitaxy", Technical Report of IEICE., Vol. 101, No. 82, pgs. 13-18, 2001.				
/MG/	AV	YASUDA, K. et al., "MOVPE growth of (100) CdZnTe Layers Using DiPZn", Journal of Crystal Growth, Vol. 159, pgs. 121-125, 1996.				
/MG/	AW	UCHIDA, Kei et al., "Study on Detector for Detecting Large Images of Both CdTe- x Ray and Y Ray by Using MOVPE", Dai 64 Kai Extended Abstracts, the Japan Society of Applied Physics, No. 1, pg. 245, 2003 (With Partial English Translation)				
/MG/	AX	WANG, Wen-Sheng et al., "(100) or (111) Heteroepitaxy of CdTe Layers on (100) GaAs Substrates by Organometallic Vapor Phase Epitaxy", Materials Chemistry and Physics, Vol. 51, pgs. 178-181, 1997.				
/MG/	AY	LEO, G. et al., "Influence of a ZnTe Buffer Layer on the Structural Quality of CdTe Epilayers Grown on (100) GaAs by Metalorganic Vapor Phase Epitaxy", J.Vac.Technol.B., Vol. 14, No. 3, pgs 1739-1744, 1996.				
	AZ				<input type="checkbox"/> Additional References sheet(s) attached	

Examiner

/Mark Gaworecki/

Date Considered

07/14/2007

\*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.